

Pulsed Plasma Electron Sources

Novel technology and technique of pulsed electron sources based on plasma cathodes allows to produce stable electron beams for applications and injectors of electron accelerators.

Main parameters:

1. Current density is 0.1-1000 A/cm²;
2. Voltage is 10-500 kV;
3. Diameter of beam is 0.5 – 20 cm.

Applications:

1. Accelerators.
2. Plasma sources.
3. Ozone production.
4. Surface modification of materials.
5. Plasma chemistry.
6. Microwave generation.
7. Sterilization.

